

MICRO DEVICES MANUFACTURING METHOD  
AND APPARATUS THEREFOR

ABSTRACT OF DISCLOSURE:

An exposure method according to the present invention  
5 includes a first step of forming on a substrate an alignment  
mark including a concave and convex pattern; a second  
step of forming a coat over said alignment mark and the  
other area on said substrate; a third step of flattening  
said coat; and a fourth step of applying a photosensitive  
10 material on said coat flattened by said third step and  
projecting a mask pattern thereto. The alignment mark is  
formed by said concave and convex pattern arranged with a  
pitch which is smaller than the predetermined value between  
adjacent convex portions having a width of not less than  
15 a predetermined value.